

REMARKS

Claim Rejections - 35 U.S.C. § 112

The Examiner has rejected claims 1-32 under 35 USC § 112, first paragraph, as failing to comply with the written description requirement. The Applicant has amended independent claim 1 to comply with the written description requirement. Specifically, claim 1 has been amended to claim the elements of “controlling a solvent vapor concentration of a control gas to be between approximately 42% and 80%.” This range for the solvent vapor concentration of a control gas is supported in the Applicant’s paragraph 5 where it is stated that “[t]ypically photoresist coating uniformity of the order of 15 to 20 angstroms within a wafer...is required” and in the Applicant’s Figure 26 where the graph illustrates that for a wafer uniformity of the order of 15 to 20 within a wafer, and a post-deposition spin speed range of 1500 rpm and 3000 rpm, the solvent concentration may be between approximately 42% and 80%.

If there are any additional charges, please charge Deposit Account No. 02-2666.

Respectfully submitted,

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